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PTO FORM 4/92		ATTY. DOCKET	CM2495CL	SERIAL NO.	10/614,591
FORM PTO-1449		APPLICANT	David A. Akerman et al		
LIST OF PATENTS AND PUBLICATIONS		FILING DATE	July 7, 2003	GROUP	1751
FOR APPLICANT'S INFORMATION		FOR Halogenated and Sulfonated Azodyes			
DISCLOSURE STATEMENT					

UNITED STATES LETTERS PATENT

JAN 15 2006		DOCUMENT NUMBER							DATE	NAME	CLASS	SUB CLASS
ME	ab	4	4	9	2	6	5	4	Jan. 8, 1985	Hoyer et al		
ME	ab	4	6	2	2	3	9	0	Nov. 11, 1986	Meininger et al		
ME	ac	6	2	8	1	3	4	0	Aug. 28, 2001	Eichhorn		

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER							DATE	COUNTRY	CLAS S	SUB CLASS
ME	ad	62-	0	8	6	0	7	0	Apr. 20, 1987	Japan (w/English translation)		
	ae	62-	0	8	6	0	7	2	Apr. 20, 1987	Japan (w/English translation)		
	af	63-	2	8	9	0	7	9	Nov. 25, 1988	Japan (English translation)		
	ag	0	1	3	7	3	2	8	Sep. 30, 1987	Poland (English translation)		
	ah	0	3	8	6	4	2	6	Sep. 5, 1990	Europe (w/English translation)		
	ai	1	0	4	6	6	7	7	Oct. 25, 2000	Europe		
	aj	0	0	4	8	3	5	5	Mar. 31, 1982	Europe		
	ak	0	0	6	3	2	7	6	Oct. 27, 1982	Europe (w/English abstract)		
ME	al	0	0	3	1	0	9	9	Jul. 1, 1981	Europe (w/English abstract)		

OTHER ART (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

ME	am	Sebe et al, <i>Revue Roumaine de Chime</i> , 38(9):1083-1089 (1993) (including English abstract)
	an	Seshadri et al, <i>Textile Research Journal</i> , 1111-1114 (1970)
	ao	<i>Chemical Abstracts</i> , 91:6386f (1979)
	ap	<i>Chemical Abstracts</i> , 108:39827y (1988)
	aq	<i>Chemical Abstracts</i> , 111:80104k (1988)
	ar	<i>Chemical Abstracts</i> , 74:88639b (1971)
	as	<i>Chemical Abstracts</i> , 121:257905g (1994)
	at	<i>Chemical Abstracts</i> , 114:64244n (1991)
	au	<i>Chemical Abstracts</i> , 108:39826x (1988)
ME	av	Patent Abstracts of Japan of S-32908 dated February 9, 1993

EXAMINER *ME/MSman* DATE CONSIDERED *4.12.04*
 EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.